Shinichi Ike

List of Publications by Year in descending order

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1684188 1588992 14 66 5 8 citations h-index g-index papers 14 14 14 82 citing authors all docs docs citations times ranked

#	Article	IF	Citations
1	Epitaxial GeSn: impact of process conditions on material quality. Semiconductor Science and Technology, 2018, 33, 114010.	2.0	20
2	Characterization of locally strained Ge1 \hat{a} ' <i>>x</i> >Sn <i>x</i> /Ge fine structures by synchrotron X-ray microdiffraction. Applied Physics Letters, 2015, 106, .	3.3	11
3	Epitaxial Ge1-xSnx Layers Grown by Metal-Organic Chemical Vapor Deposition Using Tertiary-butyl-germane and Tri-butyl-vinyl-tin. ECS Solid State Letters, 2015, 4, P59-P61.	1.4	10
4	Characterization of crystallinity of Ge1â^'xSnx epitaxial layers grown using metal-organic chemical vapor deposition. Thin Solid Films, 2016, 602, 7-12.	1.8	9
5	Formation and characterization of locally strained Ge1â^'Sn /Ge microstructures. Thin Solid Films, 2014, 557, 164-168.	1.8	6
6	Analysis of Microscopic Strain and Crystalline Structure in Ge/Ge1-XSnx Fine Structures by Using Synchrotron X-ray Microdiffraction. ECS Transactions, 2016, 75, 769-775.	0.5	3
7	Selective epitaxial growth of Ge $1\hat{a}$ °x Sn x on Si by using metal-organic chemical vapor deposition. Journal of Crystal Growth, 2017, 468, 614-619.	1.5	3
8	(Invited) Challenges of Energy Band Engineering with New Sn-Related Group IV Semiconductor Materials for Future Integrated Circuits. ECS Transactions, 2015, 69, 89-98.	0.5	2
9	Selective growth of Ge1â^'xSnxepitaxial layer on patterned SiO2/Si substrate by metalâ€"organic chemical vapor deposition. Japanese Journal of Applied Physics, 2018, 57, 01AC05.	1.5	1
10	Epitaxial growth of heavily doped n+-Ge layers using metal-organic chemical vapor deposition with in situ phosphorus doping. Thin Solid Films, 2018, 645, 57-63.	1.8	1
11	Characterization of Local Strain Structures in Heteroepitaxial Ge1-xSnx/Ge Microstructures by Using Microdiffraction Method. ECS Transactions, 2013, 58, 185-192.	0.5	0
12	Influence of precursor gas on SiGe epitaxial material quality in terms of structural and electrical defects. Japanese Journal of Applied Physics, 2016, 55, 04EJ11.	1.5	0
13	In situphosphorus-doped Ge1â^'xSnxlayers grown using low-temperature metal-organic chemical vapor deposition. Semiconductor Science and Technology, 2017, 32, 124001.	2.0	0
14	Evaluation of User Support of a Hemispherical Sub-display with GUI Pointing Functions. Lecture Notes in Computer Science, 2011, , 436-445.	1.3	0